

Dr. Ping Hsu

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Ping Hsu is the Global PCMP R&D Director at Advanced Cleans & Slurry Technologies (ACST), Qnity, where he leads global research and development for post-chemical mechanical planarization (post-CMP) cleaning technologies. With experience spanning industrial research, application engineering, formulation development, and technical leadership, he has played a key role in advancing cleaning solutions for leading-edge semiconductor processes.

Dr. Hsu began his career as an associate researcher at the Industrial Technology Research Institute and later worked as an application engineer at Eastman Kodak. He joined the DuPont in 2011 as an R&D chemist and subsequently advanced through technical and leadership roles within Qnity. Over the past decade, he has led multiple generations of post-CMP cleaning innovations that have supported approximately tenfold business growth, with a substantial portion enabled by products developed under his technical leadership. Notably, he led the development of the first ruthenium-compatible post-CMP cleaner for advanced logic applications. In addition to product innovation, Dr. Hsu has also developed laboratory methodologies that strengthen mechanistic understanding, accelerate development cycles, and translate surface science into practical semiconductor process solutions. His contributions include publications, conference presentations, inventions, and trade-secret discoveries related to post-CMP cleaning and surface-interaction mechanisms.

Dr. Hsu earned his Ph.D. in Polymer Science from The University of Akron, an M.S. in Chemistry from National Taiwan University, and a B.S. in Chemistry from National Tsing Hua University. He is passionate about translating scientific innovation into industrial impact and fostering collaborative R&D teams that advance next-generation semiconductor technologies.